

Fig.1

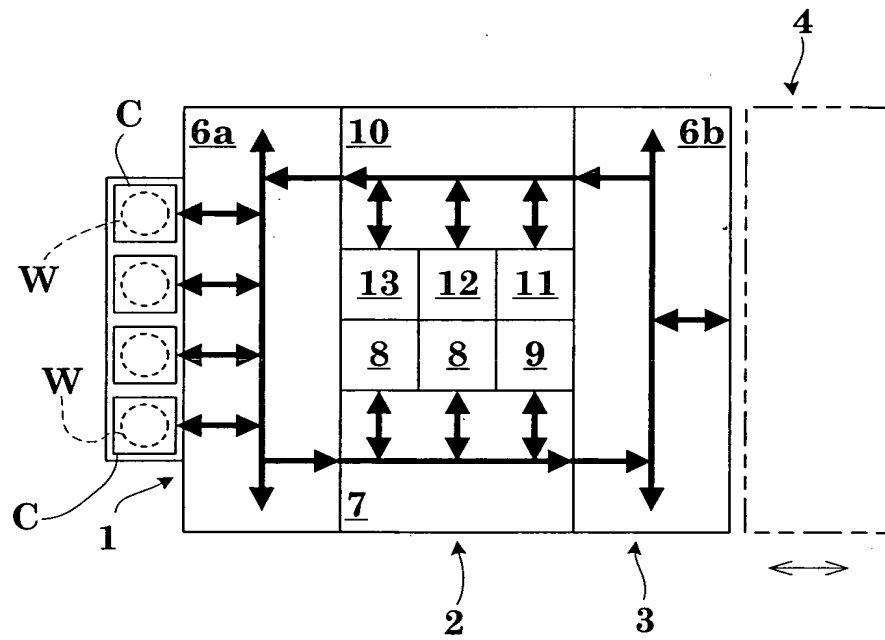


Fig.2

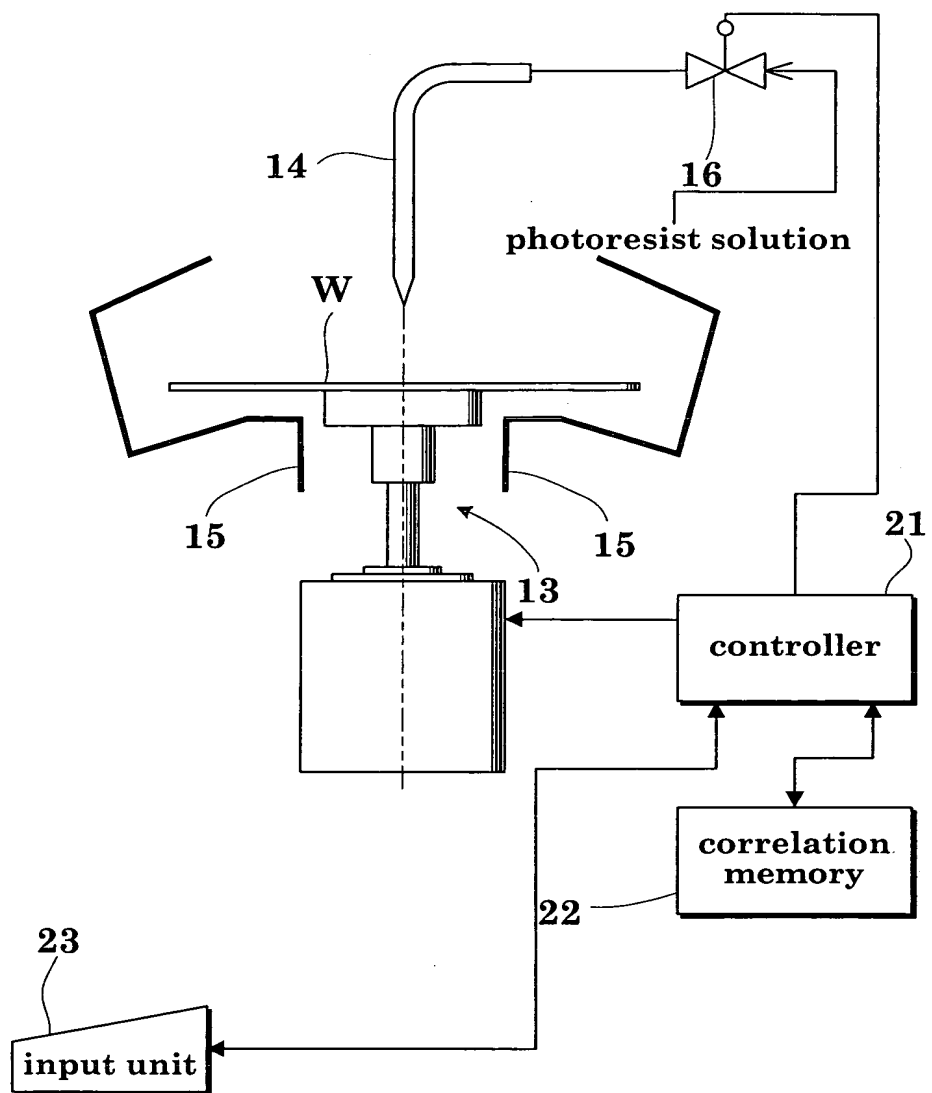


Fig.3

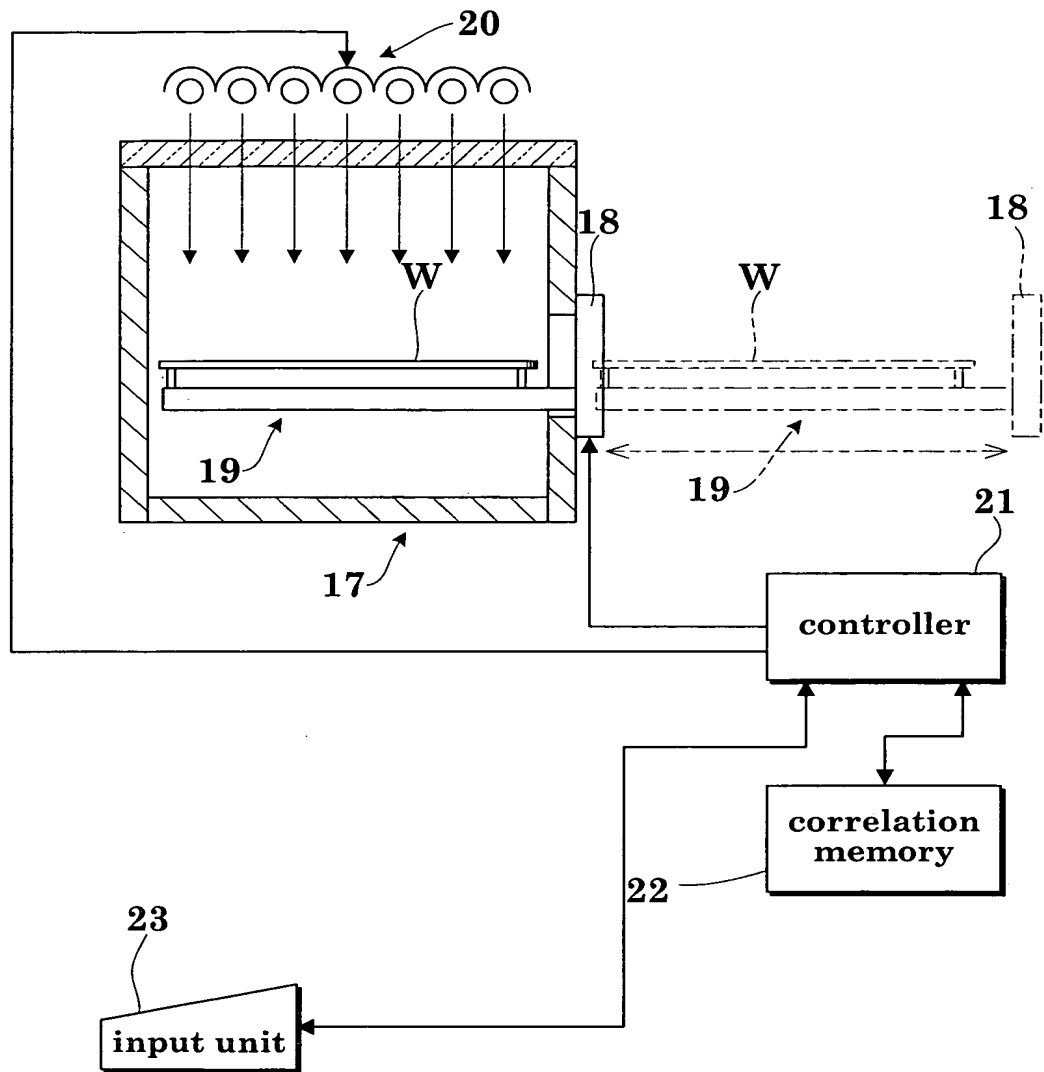


Fig.4

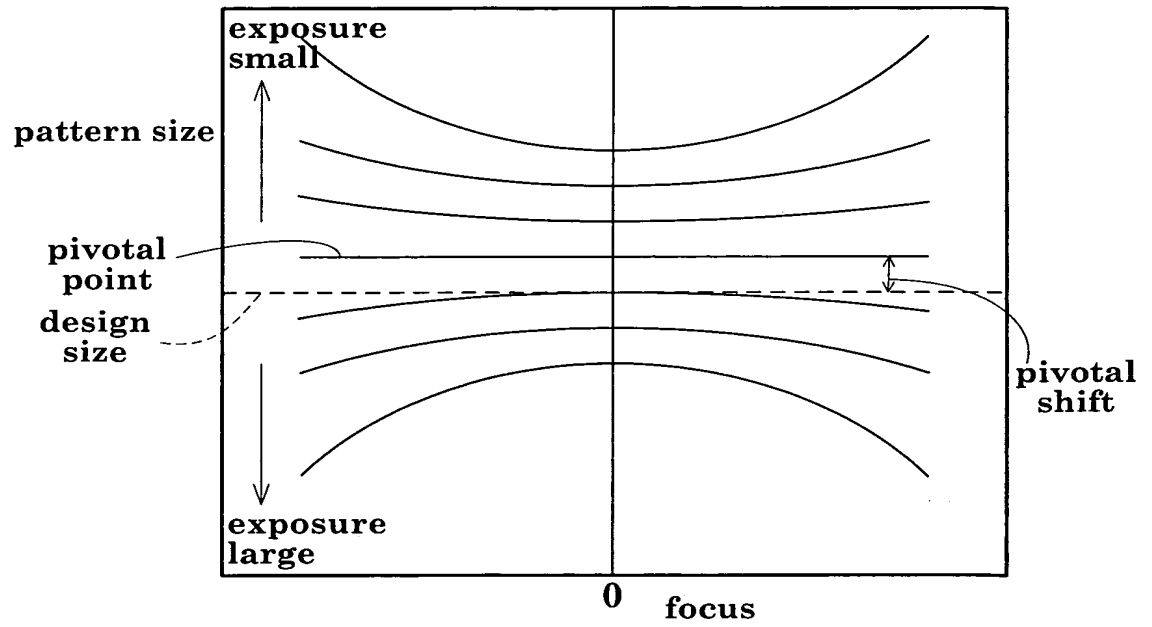


Fig.5

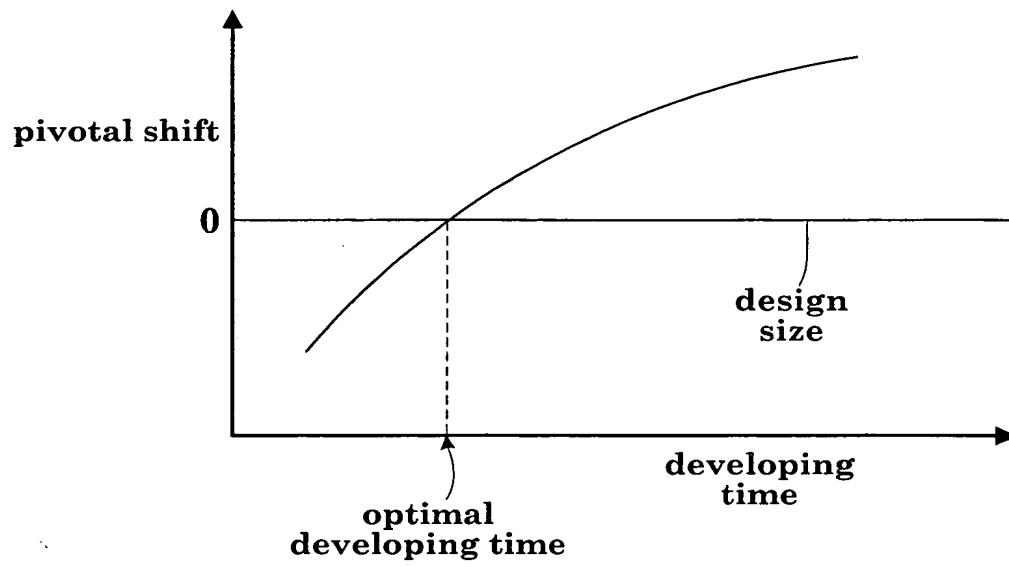


Fig.6

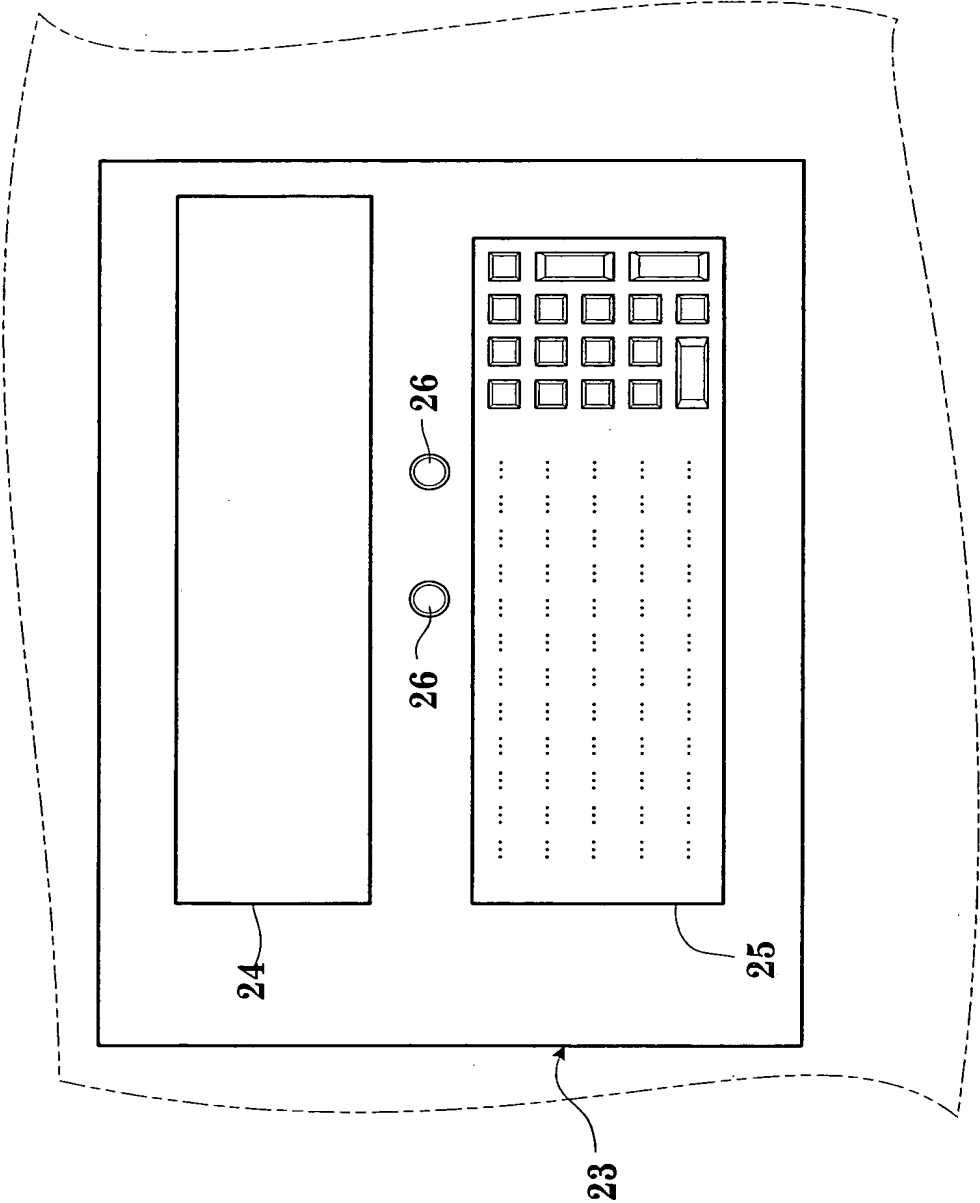


Fig.7

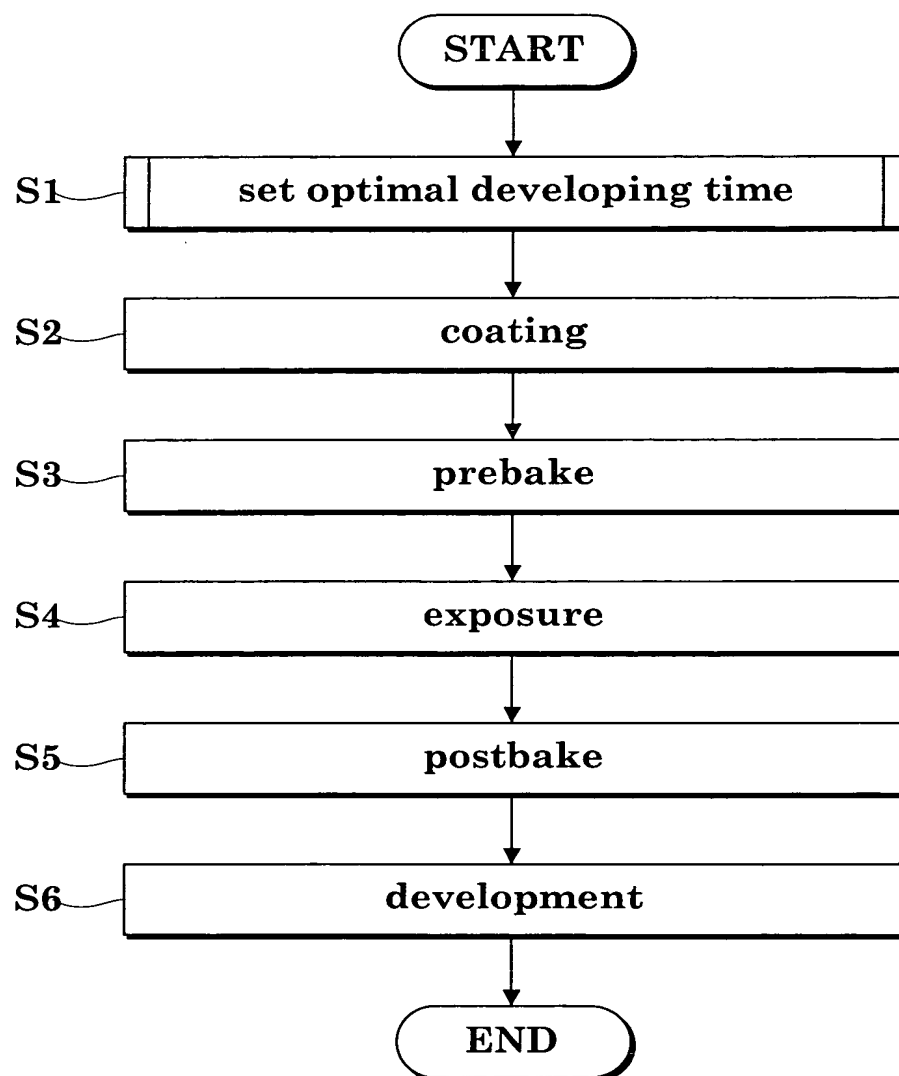


Fig.8

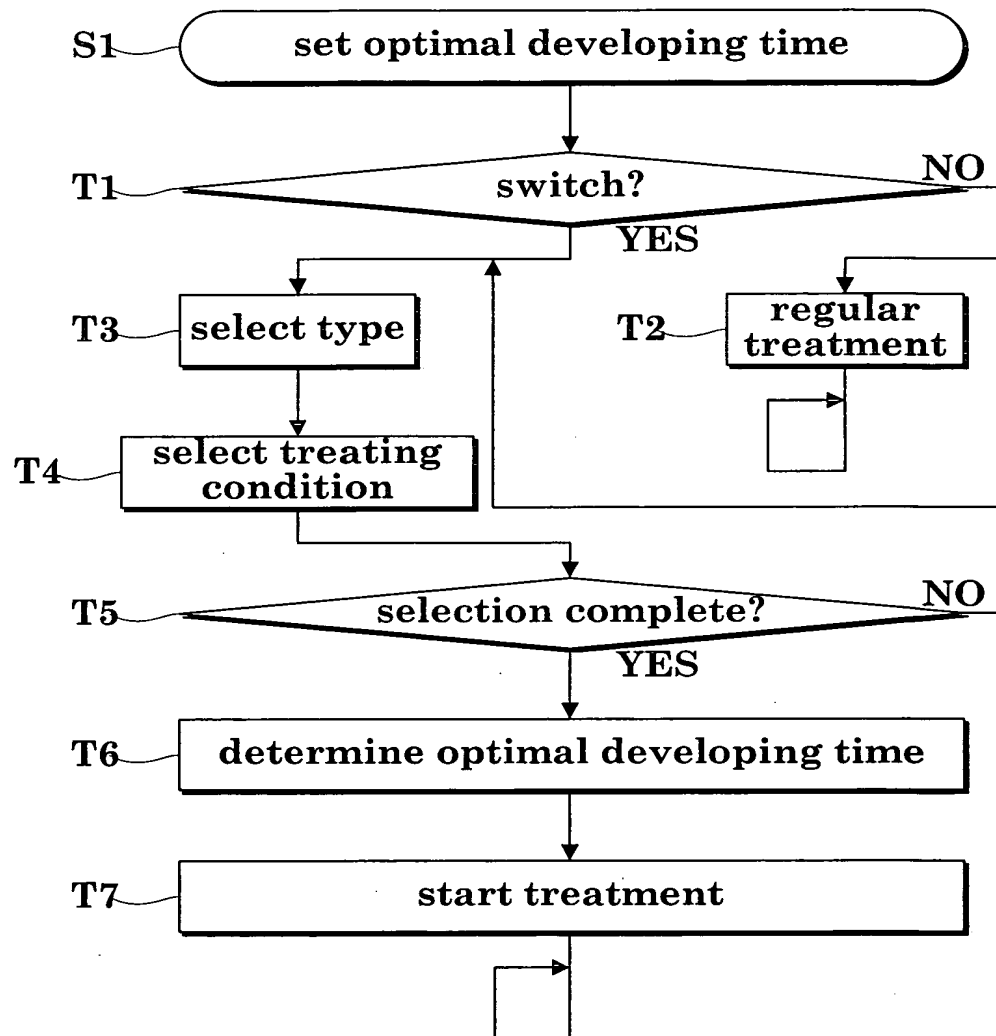


Fig.9

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Switch substrate treating conditions?

- (1) switch
- (2) not switch

Fig.10

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Which type to select?

- 1. type of photoresist
- 2. type of pattern size
- 3. type of pattern shape

Fig.11

24

1. type of photoresist

- A. ...
- B. ...
- C. ...

Fig.12

24

2. type of pattern size

- a. ...
- b. ...
- c. ...

Fig.13

24

3. type of pattern shape

X. ...

Y. ...

Z. ...

Fig.14

24

Selection complete?

Fig.15

24

Optimal developing time is

Substrate treating conditions: A. ...

c. ...

Y. ...

Fig.16

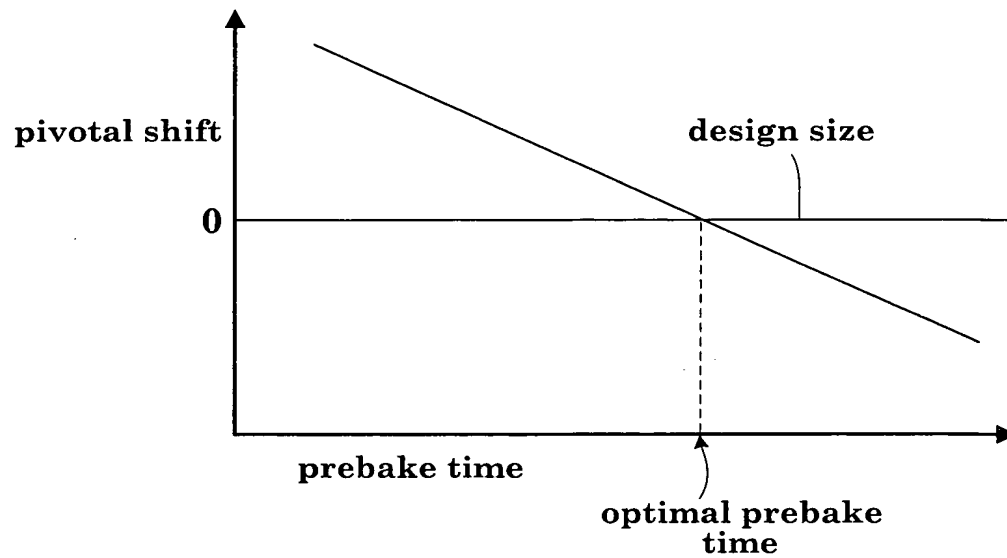


Fig.17

